

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L5	0	((polytmethyl adj methacrylate) near (polyacrylic adj acid)) or ((polytmethyl adj acrylate) near (polyacrylic adj acid)) or ((polydimethyl adj acrylate) near (polymethyl adj acrylate)) or ((polytdimethyl adj acrylate) near (polytmethyl adj methacrylate)) or (polytvinyl adj pyrrolidone) or (polytdimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:58
L6	0	((polytmethyl adj methacrylate) near (acrylic adj acid)) or ((polytmethyl adj acrylate) near (acrylic adj acid)) or ((polydimethyl adj acrylate) near (methyl adj acrylate)) or ((polytdimethyl adj acrylate) near (methyl adj methacrylate)) or (polytvinyl adj pyrrolidone) or (polytdimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:58
L7	15034	((methyl adj methacrylate) near (acrylic adj acid)) or ((methyl adj acrylate) near (acrylic adj acid)) or ((dimethyl adj acrylate) near (methyl adj acrylate)) or ((dimethyl adj acrylate) near (methyl adj methacrylate)) or (vinyl adj pyrrolidone) or (dimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:57
L8	23434	((polymethyl adj methacrylate) near (acrylic adj acid)) or ((polymethyl adj acrylate) near (acrylic adj acid)) or ((polydimethyl adj acrylate) near (methyl adj acrylate)) or ((polydimethyl adj acrylate) near (methyl adj methacrylate)) or (polyvinyl adj pyrrolidone) or (polydimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:57
L9	23434	((polymethyl adj methacrylate) near (acrylic adj acid)) or ((polymethyl adj acrylate) near (acrylic adj acid)) or ((polydimethyl adj acrylate) near (methyl adj acrylate)) or ((polydimethyl adj acrylate) near (methyl adj methacrylate)) or (polyvinyl adj pyrrolidone) or (polydimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 19:01

## EAST Search History

L10	23453	((polymethyl adj methacrylate) near (polyacrylic adj acid)) or ((polymethyl adj acrylate) near (polyacrylic adj acid)) or ((polydimethyl adj acrylate) near (polymethyl adj acrylate)) or ((polydimethyl adj acrylate) near (polymethyl adj methacrylate)) or (polyvinyl adj pyrrolidone) or (polydimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:58
L11	23564	8 or 9 or 10	USPAT	OR	ON	2006/09/01 18:59
L12	73628	photoresist	USPAT	OR	ON	2006/09/01 18:59
L13	1	11 near 12	USPAT	OR	ON	2006/09/01 19:02
L14	0	7 near 12	USPAT	OR	ON	2006/09/01 19:01
L15	24222	((polymethyl adj methacrylate) with (acrylic adj acid)) or ((polymethyl adj acrylate) with (acrylic adj acid)) or ((polydimethyl adj acrylate) with (methyl adj acrylate)) or ((polydimethyl adj acrylate) with (methyl adj methacrylate)) or (polyvinyl adj pyrrolidone) or (polydimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 19:25
L16	32	15 with 12	USPAT	OR	ON	2006/09/01 19:16
L17	0	16 and gas near absorbing	USPAT	OR	ON	2006/09/01 19:05
L18	0	16 and (gas near absorbing)	USPAT	OR	ON	2006/09/01 19:05
L19	0	15 with ("193" adj nm adj photo adj resist)	USPAT	OR	ON	2006/09/01 19:16
L20	1	("193" adj nm adj photo adj resist)	USPAT	OR	ON	2006/09/01 19:16
L21	4	"193" near (photo adj resist)	USPAT	OR	ON	2006/09/01 19:17
L22	133	"193" near (photoresist)	USPAT	OR	ON	2006/09/01 19:17
L23	135	21 or 22	USPAT	OR	ON	2006/09/01 19:17
L24	0	23 with 15	USPAT	OR	ON	2006/09/01 19:17
L25	2	23 and 15	USPAT	OR	ON	2006/09/01 19:18
L26	647	15 and 12	USPAT	OR	ON	2006/09/01 19:26
L27	0	26 and (gas adj absorbing)	USPAT	OR	ON	2006/09/01 19:26
L28	387	26 and (water adj soluble)	USPAT	OR	ON	2006/09/01 19:27
L29	150	26 and (water adj soluble adj polymer)	USPAT	OR	ON	2006/09/01 19:27
L30	73	29 and resist	USPAT	OR	ON	2006/09/01 19:27
L31	30	30 and semiconductor	USPAT	OR	ON	2006/09/01 20:17
L32	1	"6692892".pn.	USPAT	OR	ON	2006/09/01 20:18

## EAST Search History

S1	3091	photo near pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:36
S2	24887	photoresist near pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:36
S3	27744	S1 or S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:37
S6	15166	i-line or KrF	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:37
S7	1807	S3 and S4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S8	10744	ArF or UvU or EUF	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S9	128	S7 and S8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S10	411399	resist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S11	66	S9 and S10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:51
S12	2	"4491628".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:56

## EAST Search History

S13	1	10/719083	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:56
S14	336	("4491628").URPN.	USPAT	OR	ON	2005/08/25 08:43
S15	965	tri-level	USPAT	OR	ON	2005/08/25 08:43
S16	68113	photoresist	USPAT	OR	ON	2005/08/25 08:43
S17	21	S15 near S16	USPAT	OR	ON	2005/08/25 10:05
S18	454581	polymer	USPAT	OR	ON	2005/08/25 10:05
S19	365962	silicon	USPAT	OR	ON	2005/08/25 10:06
S20	191357	mask	USPAT	OR	ON	2005/08/25 10:06
S21	1	S18 near S19 near S20	USPAT	OR	ON	2005/08/25 10:09
S22	1	silicon near polymer near mask	USPAT	OR	ON	2005/08/25 10:09
S23	1	silicon near polymer near etch	USPAT	OR	ON	2005/08/25 10:09
S24	357	S18 near S20	USPAT	OR	ON	2005/08/25 10:14
S25	3334	i-line	USPAT	OR	ON	2005/08/25 10:14
S26	191357	mask	USPAT	OR	ON	2005/08/25 10:14
S27	2761	S25 and S26	USPAT	OR	ON	2005/08/25 10:15
S28	365962	silicon	USPAT	OR	ON	2005/08/25 10:15
S29	2131	S27 and S28	USPAT	OR	ON	2005/08/25 10:15
S30	186985	poly	USPAT	OR	ON	2005/08/25 10:15
S31	692	S29 and S30	USPAT	OR	ON	2005/08/25 10:53
S32	1874	gas near absorbing	USPAT	OR	ON	2005/08/25 10:54
S33	766	oxygen near absorbing	USPAT	OR	ON	2005/08/25 10:54
S34	200051	resist	USPAT	OR	ON	2005/08/25 10:54
S35	96988	spin	USPAT	OR	ON	2005/08/25 10:54
S36	14776	bake	USPAT	OR	ON	2005/08/25 10:54
S39	151804	water adj soluble	USPAT	OR	ON	2005/08/25 10:56
S40	454581	polymer	USPAT	OR	ON	2005/08/25 10:56
S41	20443	S39 near S40	USPAT	OR	ON	2005/08/25 10:56
S42	3403	S35 and S36	USPAT	OR	ON	2005/08/25 10:56
S43	36	S41 and S42	USPAT	OR	ON	2005/08/25 10:57
S44	30	S43 and S34	USPAT	OR	ON	2005/08/25 11:04
S46	2594	S32 or S33	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 10:57

## EAST Search History

S50	195	S34 and S46	USPAT	OR	ON	2005/08/25 11:05
S51	23	S50 and S39	USPAT	OR	ON	2005/08/25 11:14
S52	53	organic adj polysilane	USPAT	OR	ON	2005/08/25 11:14
S53	68113	photoresist	USPAT	OR	ON	2005/08/25 11:14
S54	8	S52 and S53	USPAT	OR	ON	2005/08/25 14:15
S55	0	organic adj polysilane adj photoresist	USPAT	OR	ON	2006/03/07 11:10
S56	0	organic adj polysilane adj resist	USPAT	OR	ON	2005/08/25 13:46
S57	0	organic adj polysilane near resist	USPAT	OR	ON	2005/08/25 13:46
S58	13	organic adj polysilane and resist	USPAT	OR	ON	2005/08/25 13:46
S61	1	10/712,446	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 14:16
S62	2	"5962191".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/26 08:09
S63	79	((polytmethyl adj methacrylate) or (polytmethyl adj acrylic adj acid) or (polytmethyl adj acrylate) or (polytmethyl adj acrylic adj acid) or (polytdimethyl adj acrylate) or (methyl adj acrylate) or (polytdimethyl adj acrylate) (polytmethyl adj methyl adj methacrylate) or (polytmethyl adj polytviny adj pyrrolidone) or (polytdimethyl adj acrylate)) and PGMEA	USPAT	OR	ON	2006/09/01 18:46
S64	2491	S63 and Aff or VUV or EUV	USPAT	OR	ON	2006/03/07 11:14
S65	6	S63 and (Aff or VUV or EUV)	USPAT	OR	ON	2006/03/07 11:14
S66	2	"5,702,776".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:44
S67	0	(silicon adj gas) near (photo adj resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:44

## EAST Search History

S68	0	(silicon adj gas) same (photo adj resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:44
S69	0	(silicon adj gas) with (photo adj resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:44
S70	18	(silicon adj gas) and (photo adj resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:45
S71	2	"20040266203"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 16:45
S72	2	"6861199".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 16:45